



[10191/3399]

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant(s) : BREITSCHWERDT et al.
Serial No. : 10/691,108
Filed : October 22, 2003
For : **DEVICE AND METHOD FOR ANISOTROPIC
PLASMA ETCHING OF A SUBSTRATE,
PARTICULARLY A SILICON ELEMENT**

Examiner : Lan VINH
Art Unit : 1765

Mail Stop Non-Fee Amendment
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

RESPONSE TO RESTRICTION REQUIREMENT

SIR:

In the Office Action dated October 24, 2005, the Examiner required restriction to one of the following inventions:

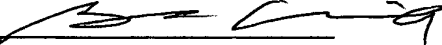
- Group I - claims 1-3
- Group II - claims 4 and 5

Accordingly, applicants hereby elect, without traverse, the claims of Group II, i.e., claims 4 and 5.

An early and favorable action on the merits is earnestly solicited.

No fee is believed to be required. However, if any fee is required, please charge to Deposit Account No. 11-0600. A duplicate copy of this sheet is enclosed.


Respectfully submitted,
KENYON & KENYON

By: 
Gerard A. Messina
Reg. No. 35,952

One Broadway
New York, NY 10004
(212) 425-7200

I hereby certify that this correspondence is being deposited with the United States Postal Service with sufficient postage as first class mail in an envelope addressed to:
Mail Stop Non-Fee Amendment
Commissioner for Patents, P.O. Box 1450, Alexandria, VA. 22313-1450
on

Date: 11/23/05

Signature: 
Gerard A. Messina
Reg. No. 35, 952.